



RTP System

UTR series



UTR-S100N-011

- Substrate size & load capacity : 4inch wafer - 1 wafer/batch
- Temperature range : RT~1,000 °C
- Substrate holder : Quartz (pin)
- Rotary pump
- Manual angle valve
- MFC: O2(1slm), N2(1slm)
- Manual control (switch panel)

Desktop type, Low Cost



UTR-S100N-012

- Substrate size & load capacity : 2inch wafer - 3 wafer/batch (2"GaN-based LED Epi-wafer on sapphire substrate)
- Temperature range : RT~1,000 °C
- Substrate holder : SiC coated graphite
- Rotary pump
- Manual angle valve
- MFC: O2(1slm), N2(1slm)
- Manual control (switch panel)

Desktop type, Low Cost



UTR-D100N-001

- Substrate size & load capacity : 4inch wafer - 1 wafer/batch
- Temperature range : RT~1,000 °C
- Double-side heating
- Substrate holder : Quartz
- ATM process
- MFC: O2(20slm), N2(20slm)
- PC control

Desktop type, Double-side Heating